

Point Curvature: Large
Aspect Ratio: Small (÷1)

## FIG. 1A PRIOR ART



Point Curvature: Little Small Aspect Ratio: Small (=4.5)

## FIG. 1B PRIOR ART



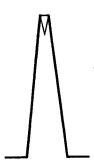
Point Curvature: Little Small Aspect Ratio: Small (=1)

FIG. 1C PRIOR ART



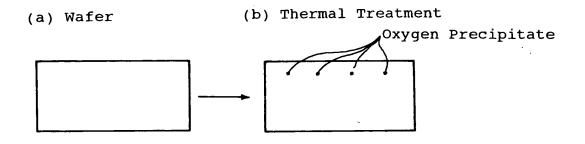
Point Curvature: Small (Several nm)
Aspect Ratio: Large (=10)

## FIG. 1D PRESENT INVENTION



Point Curvature: Small (Several nm) Aspect Ratio: Large (eq 10)

## FIG. 1E PRESENT INVENTION



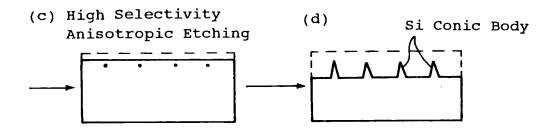
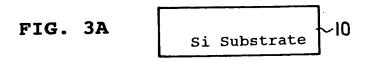
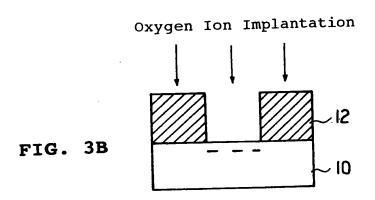
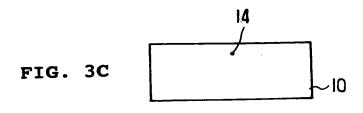
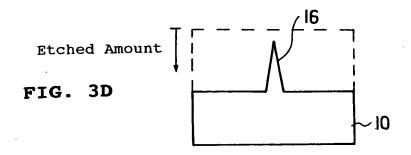


FIG. 2









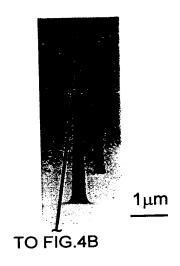


FIG.4A

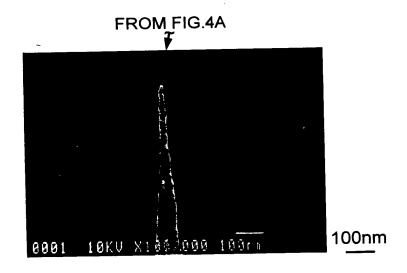


FIG.4B

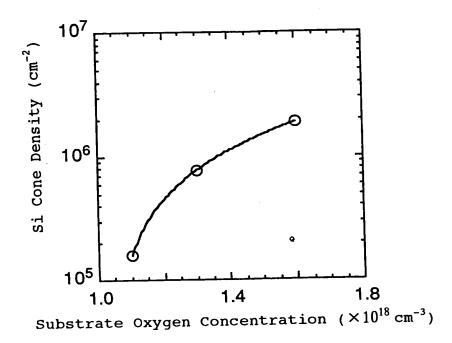


FIG. 5

B Implantation Amount:
7 X 10<sup>13</sup>cm<sup>-2</sup>

FIG.6A

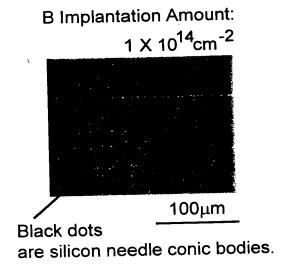
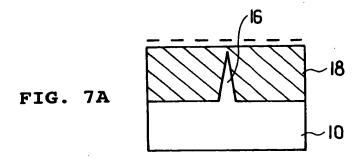
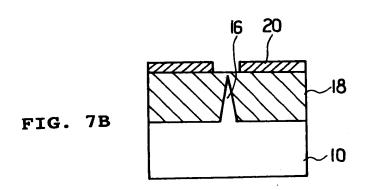
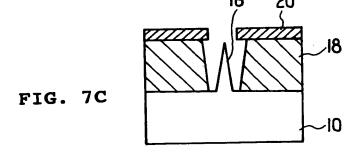
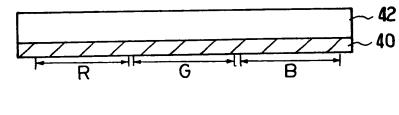


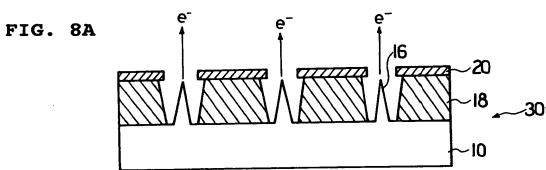
FIG.6B

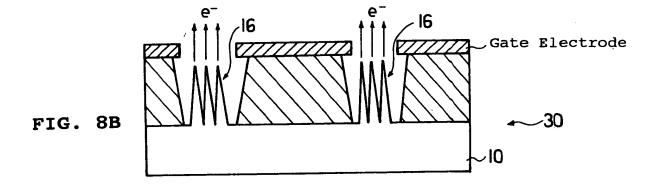












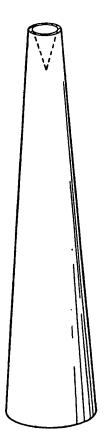
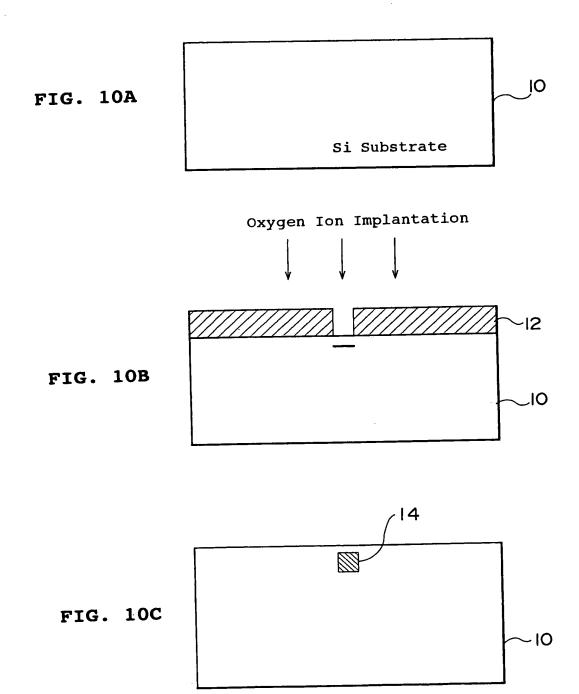
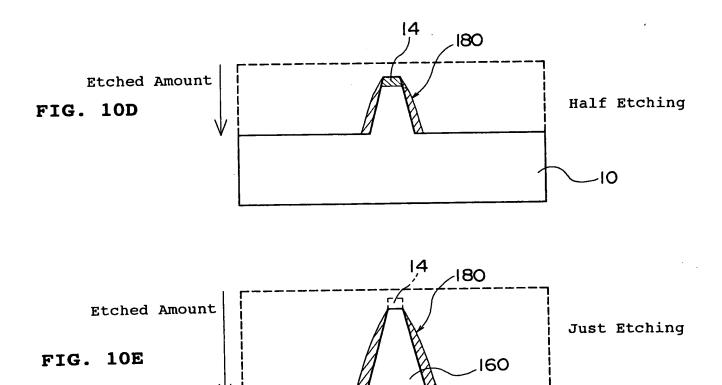


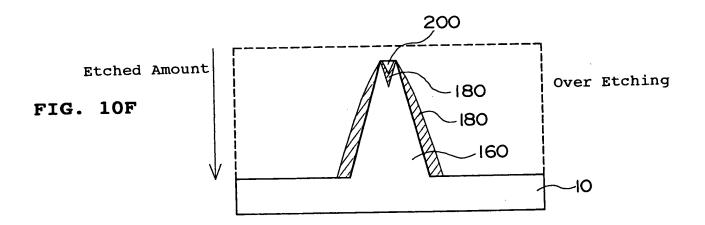
FIG. 9A



FIG. 9B







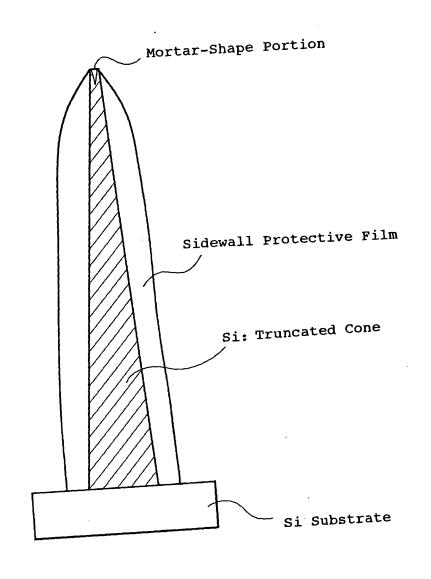
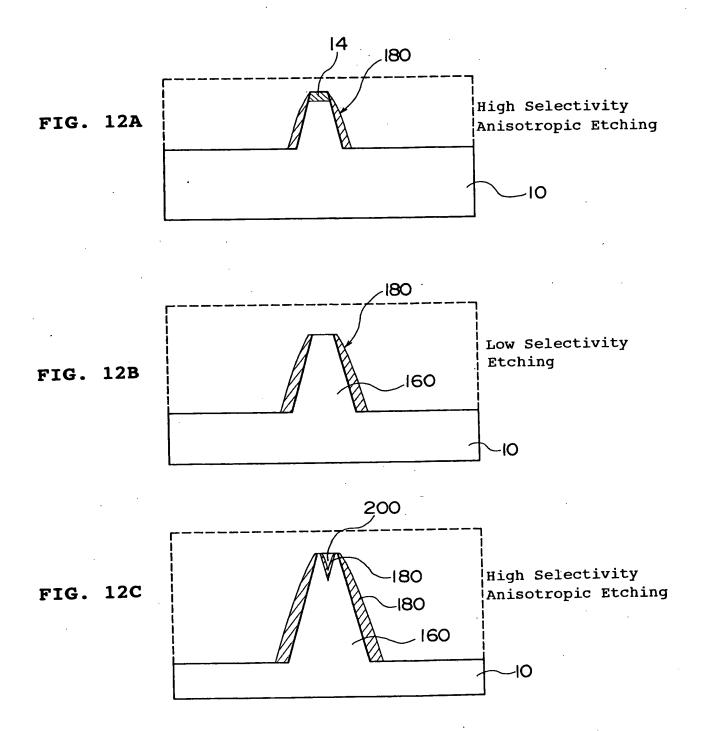
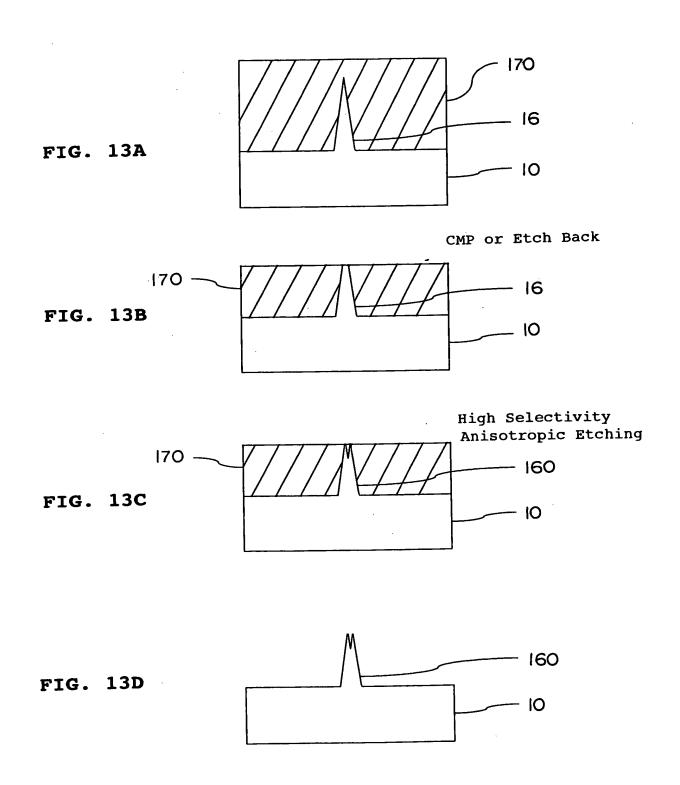


FIG. 11





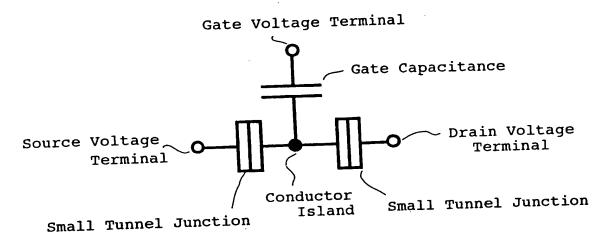


FIG. 14A PRIOR ART

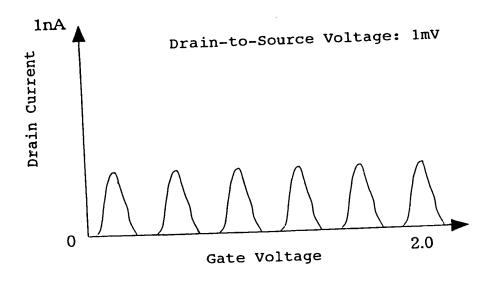


FIG. 14B PRIOR ART

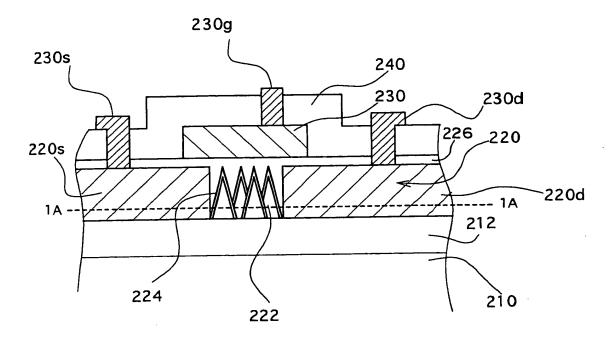


FIG. 15A

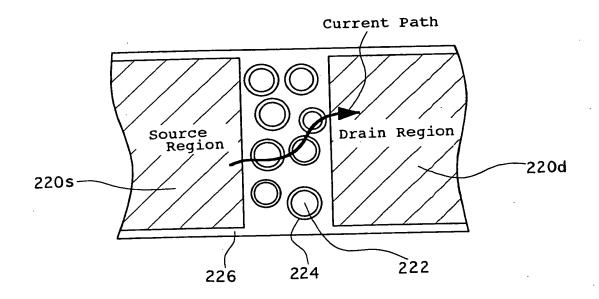
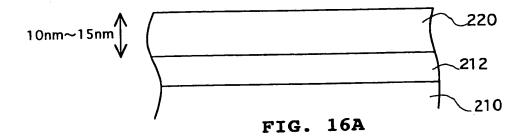
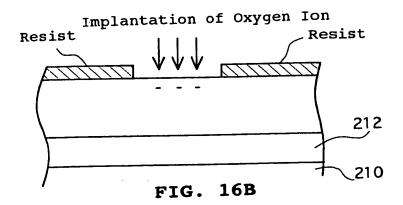
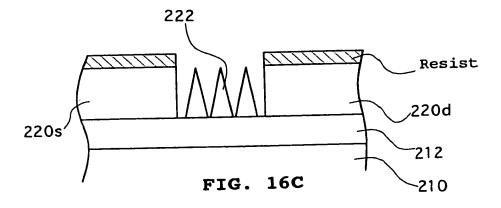
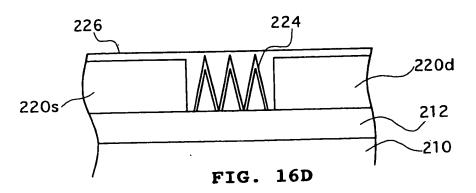


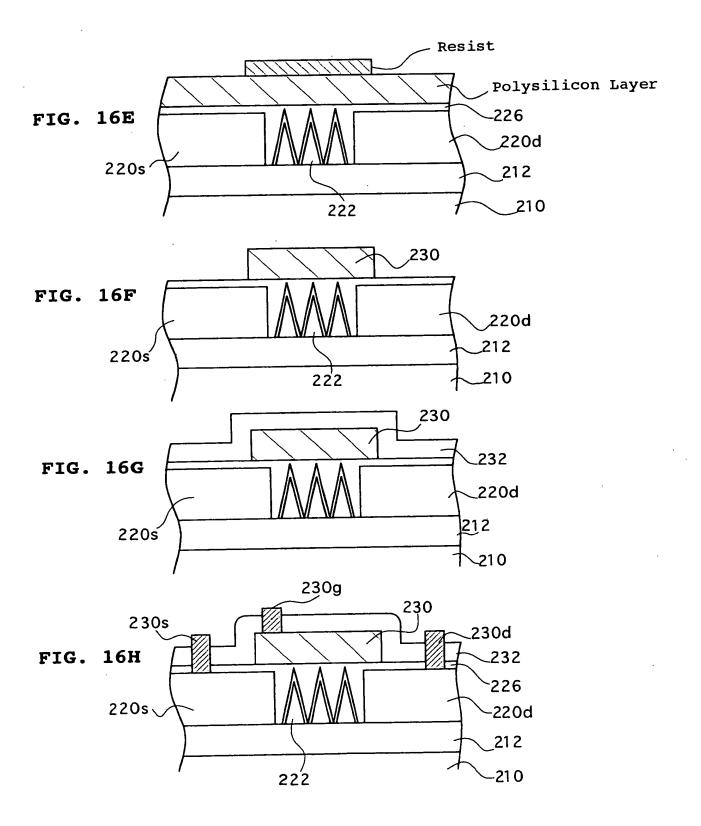
FIG. 15B

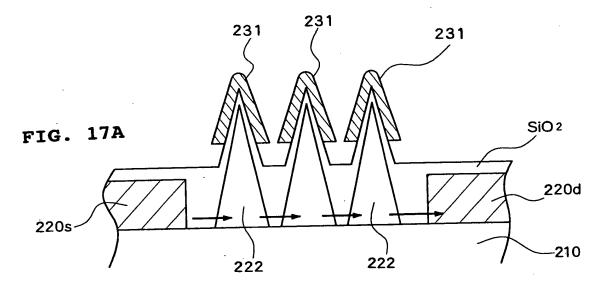




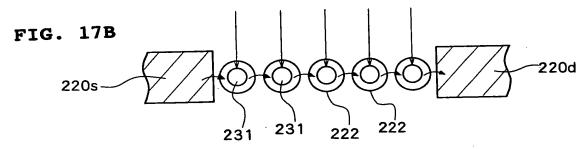


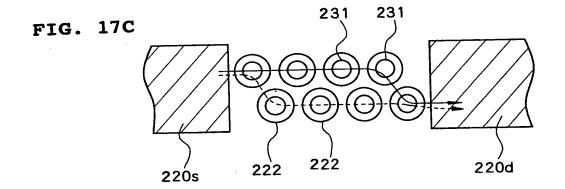






Selective Gate Control





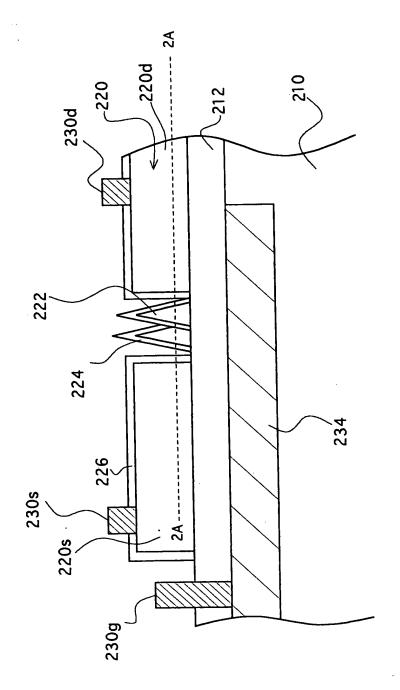


FIG. 18

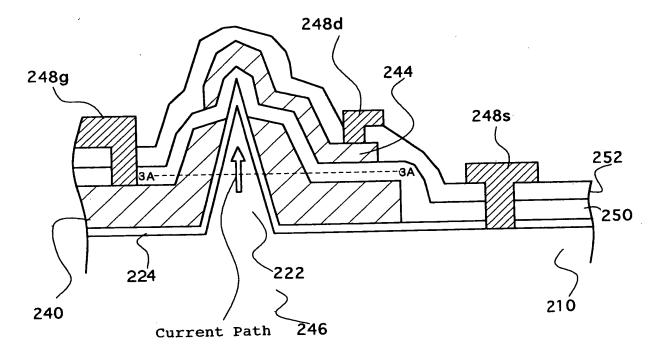


FIG. 19A

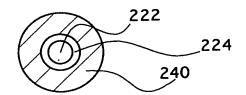
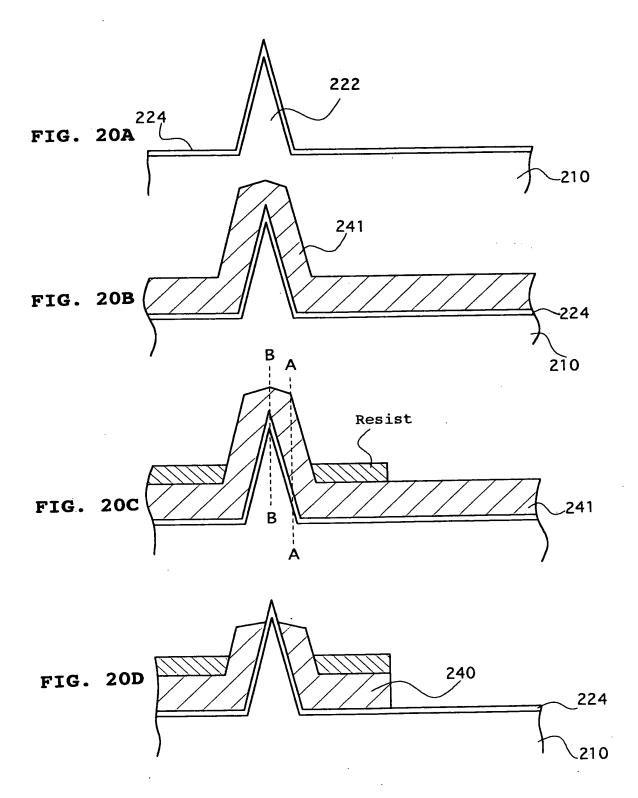
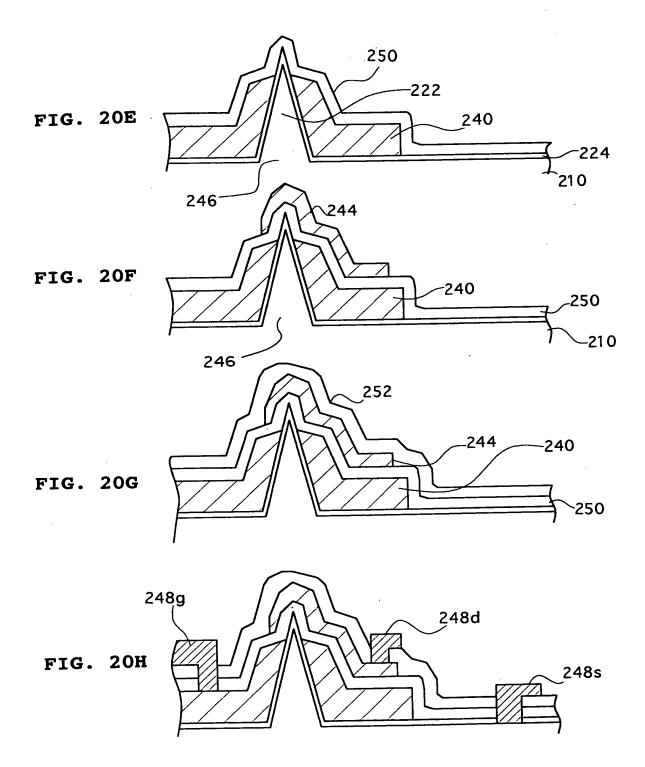


FIG. 19B





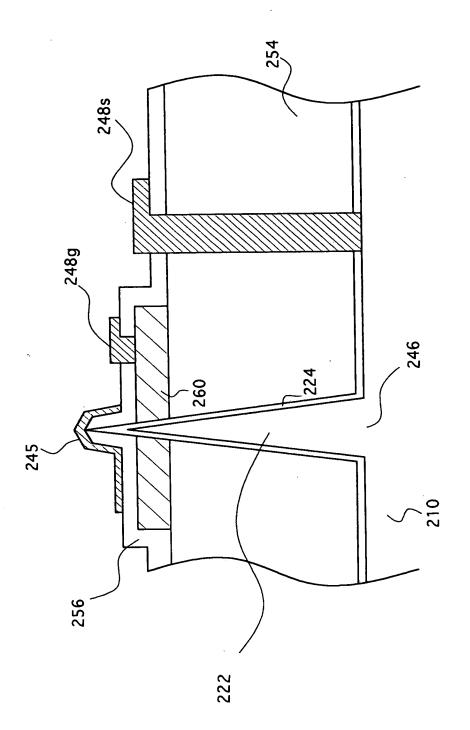


FIG. 21

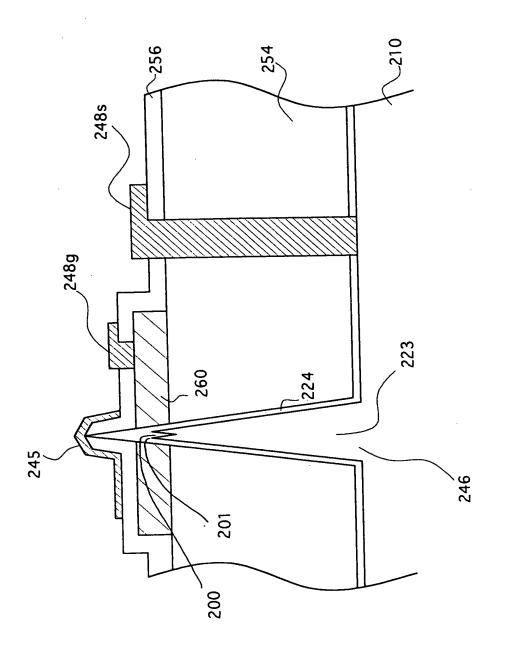
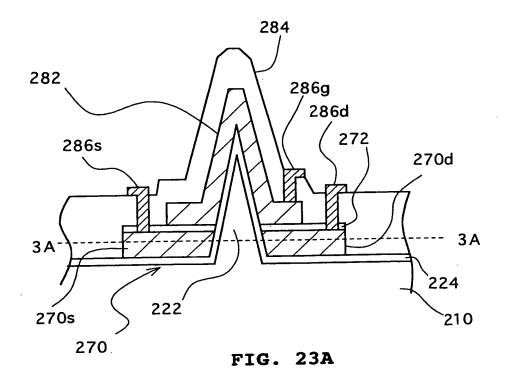


FIG. 22



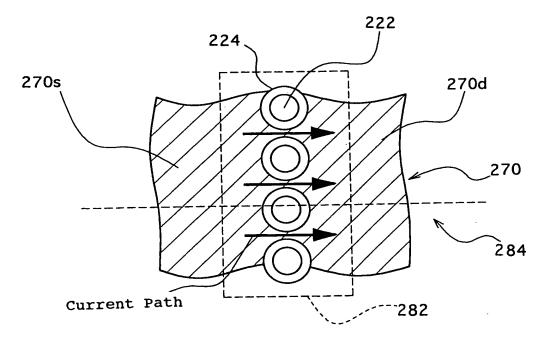


FIG. 23B

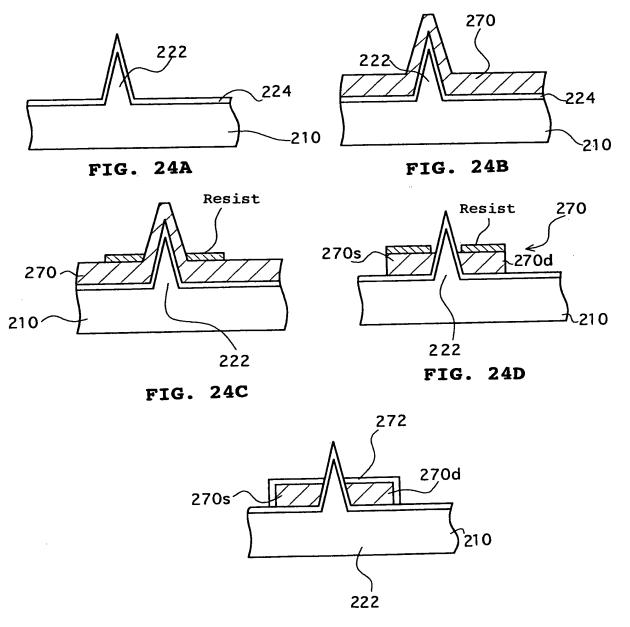
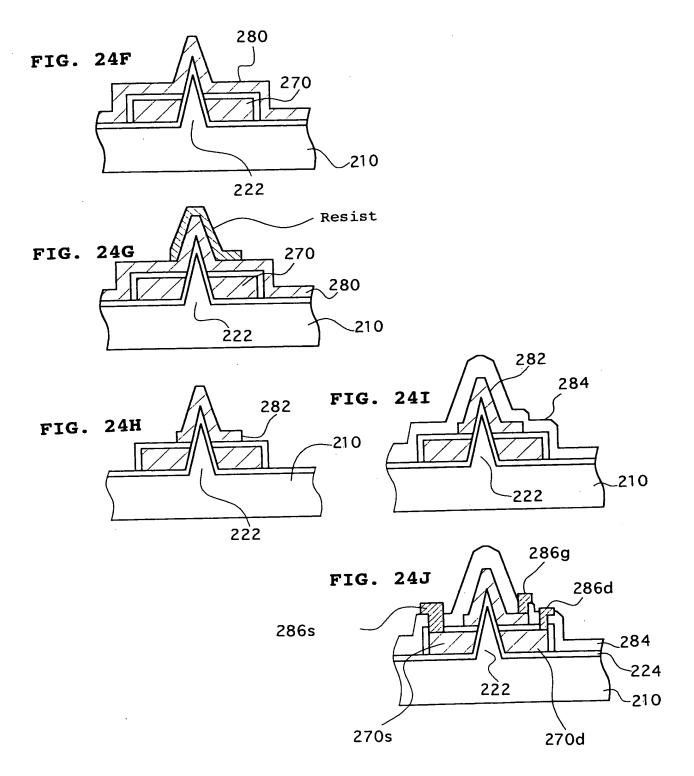


FIG. 24E



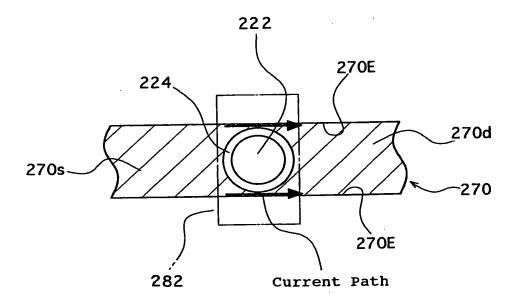


FIG. 25A

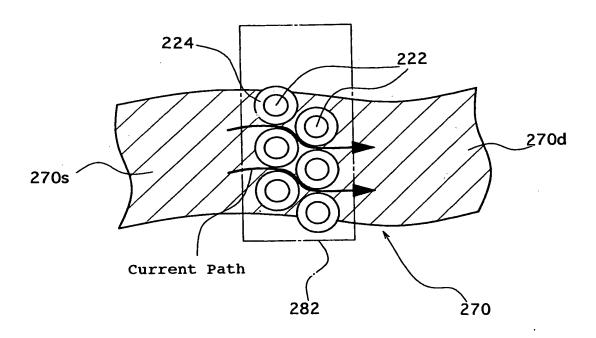


FIG. 25B

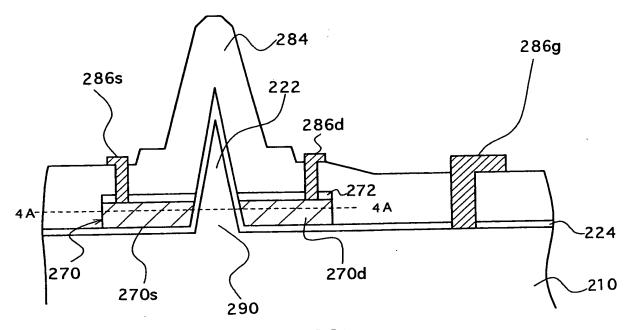


FIG. 26A

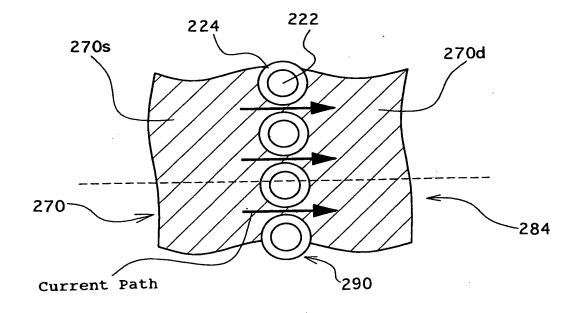


FIG. 26B

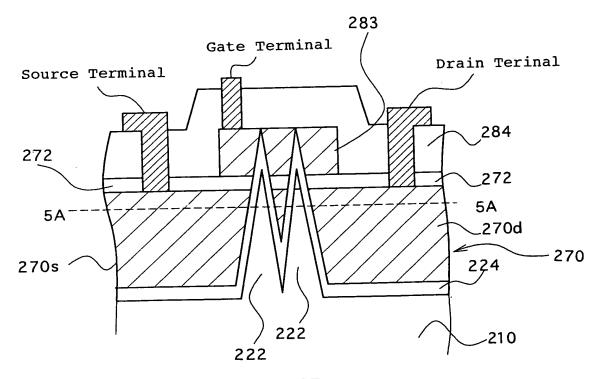


FIG. 27A

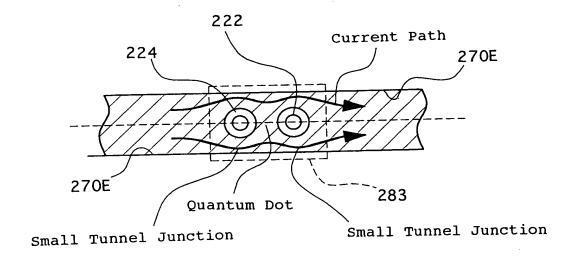


FIG. 27B

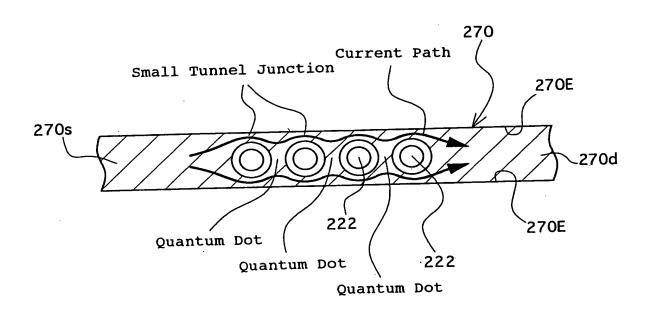


FIG. 28

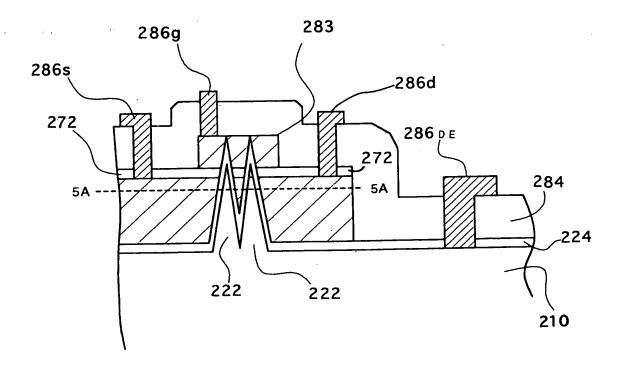


FIG. 29A

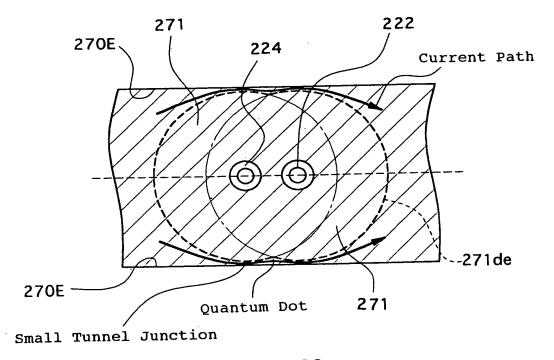


FIG. 29B

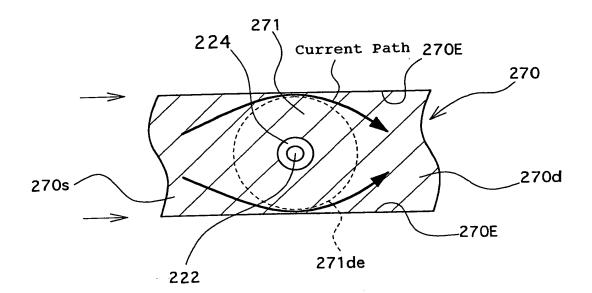


FIG. 30

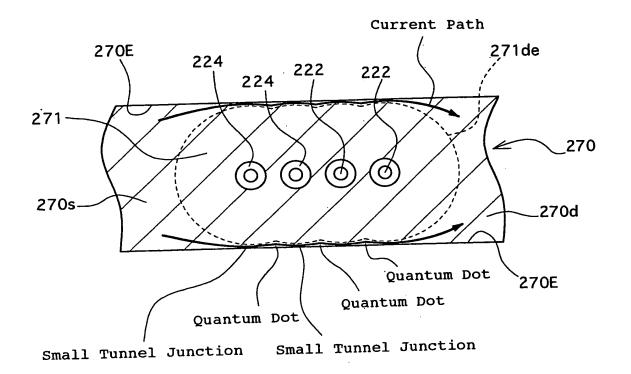


FIG. 31

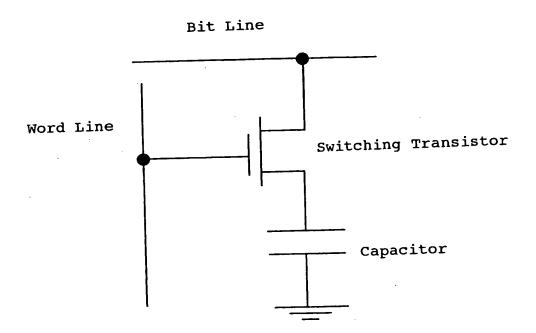


FIG. 32 PRIOR ART

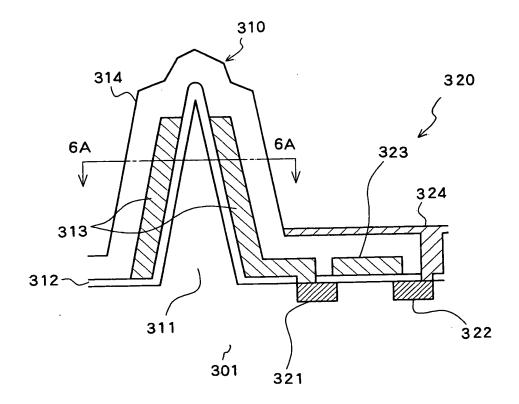


FIG. 33A

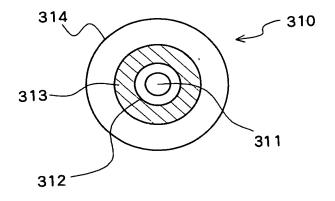


FIG. 33B

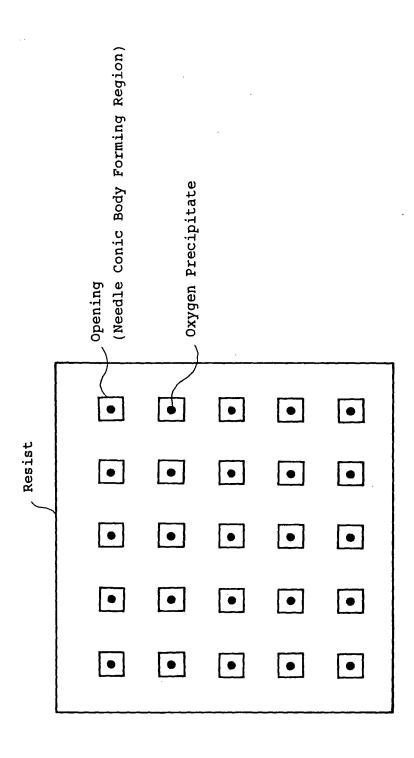
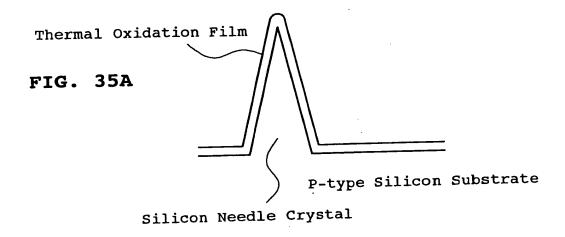
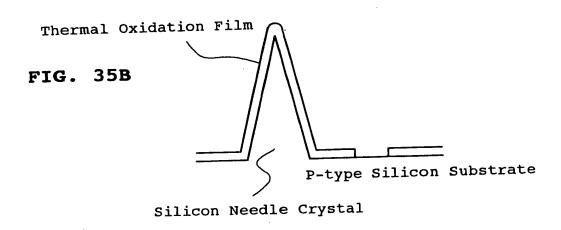
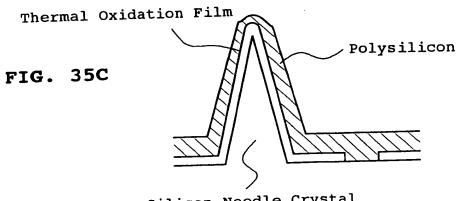


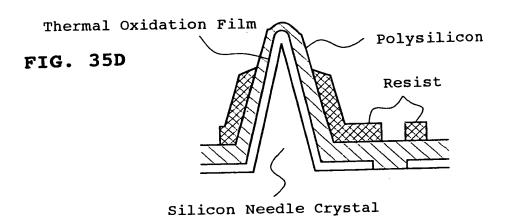
FIG. 34

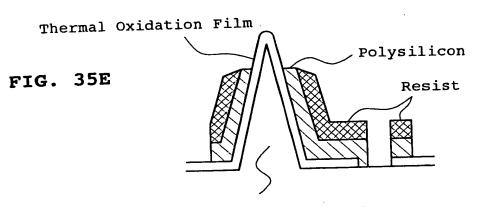




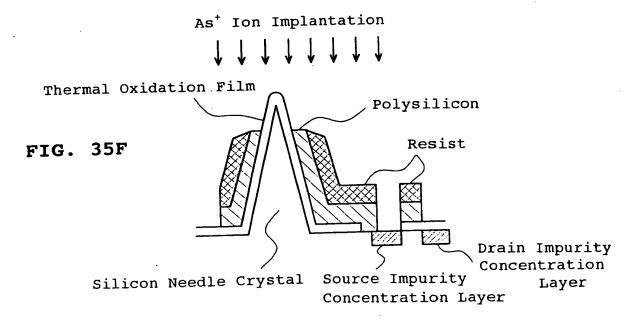


Silicon Needle Crystal





Silicon Needle Crystal



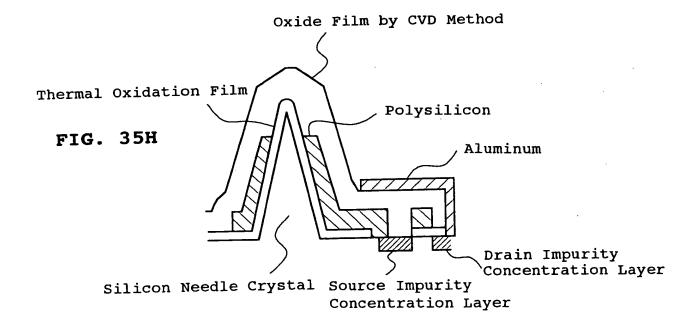
Thermal Oxidation Film

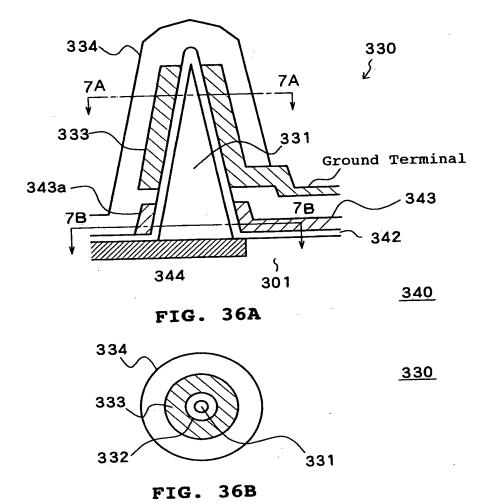
Polysilicon

FIG. 35G

Drain Impurity
Concentration Layer

Silicon Needle Crystal Source Impurity
Concentration Layer





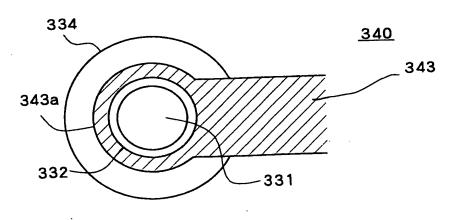
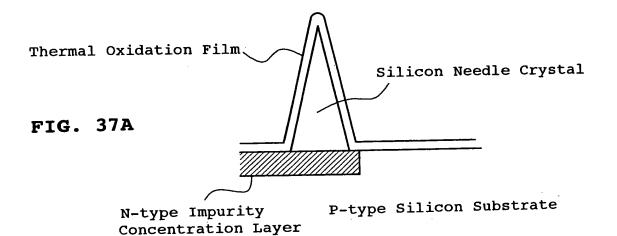
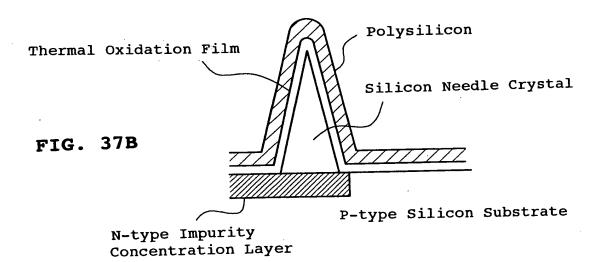
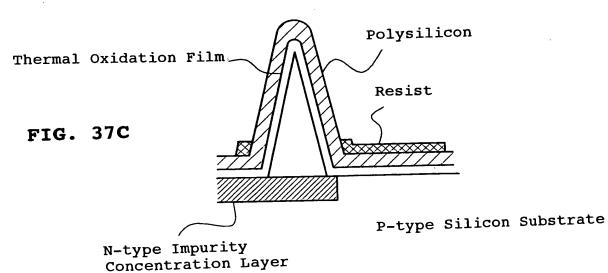
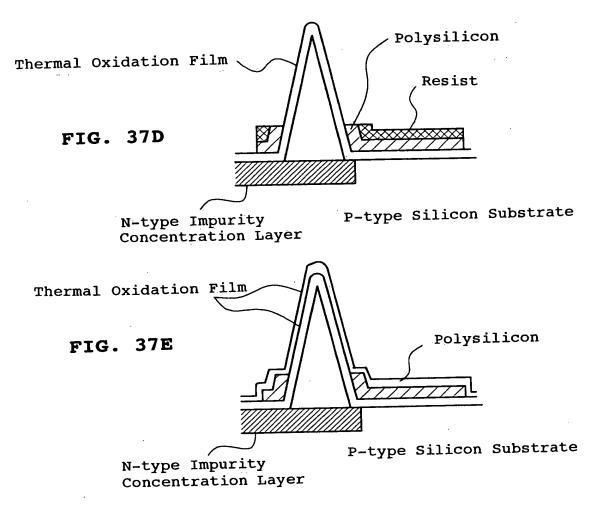


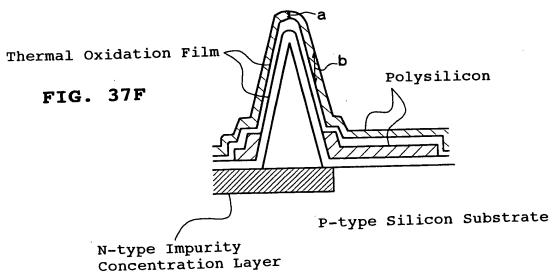
FIG. 36C

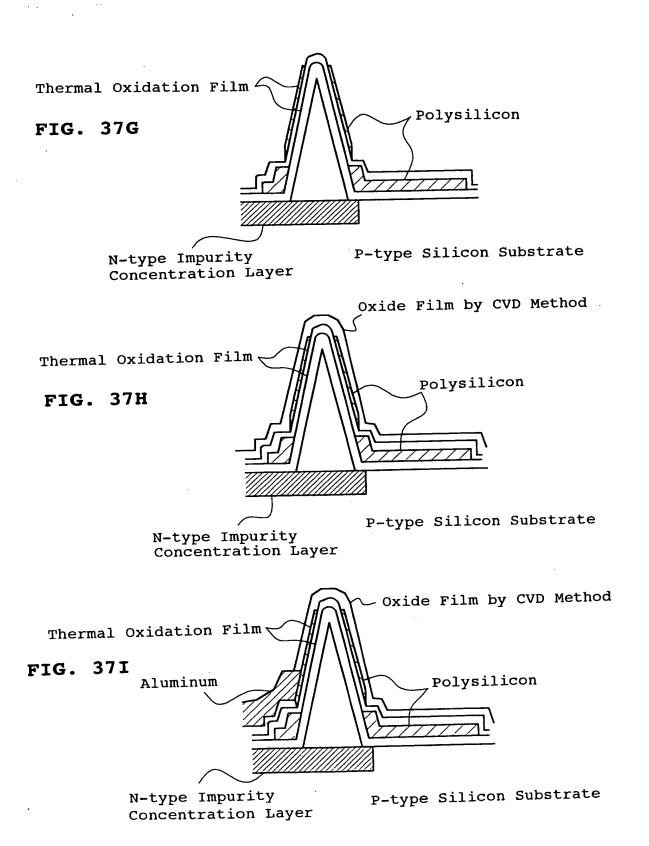


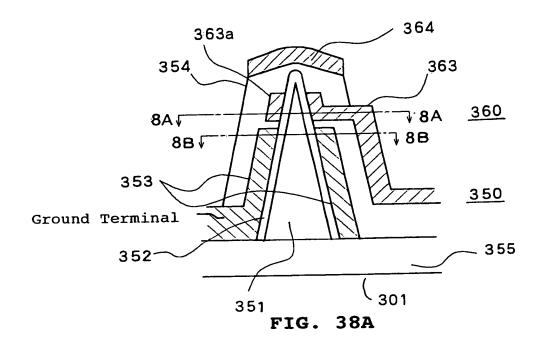












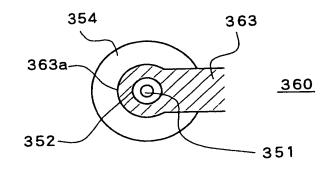


FIG. 38B

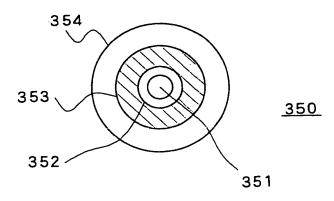


FIG. 38C

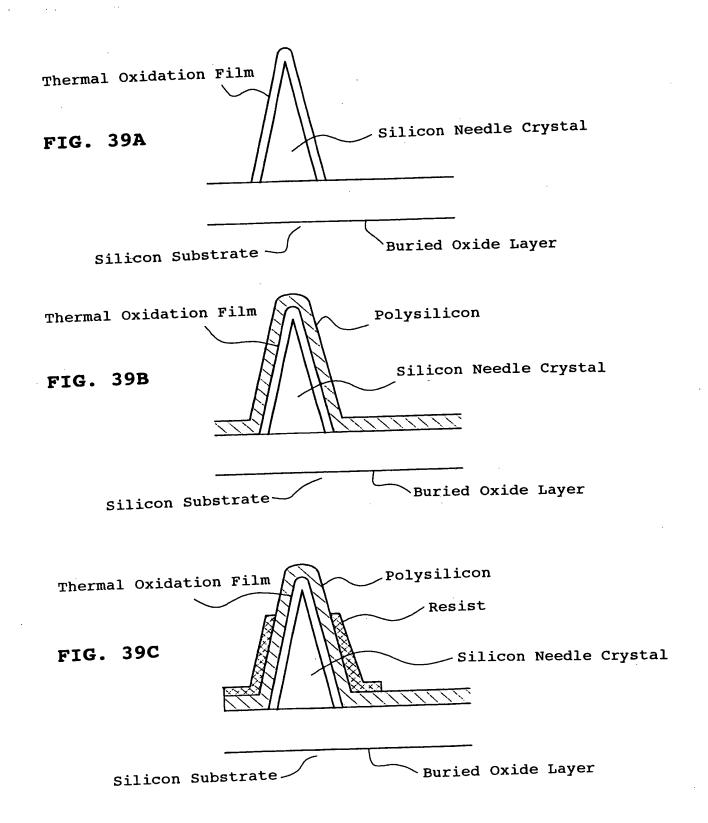


FIG. 39D

Silicon Substrate

Buried Oxide Layer

